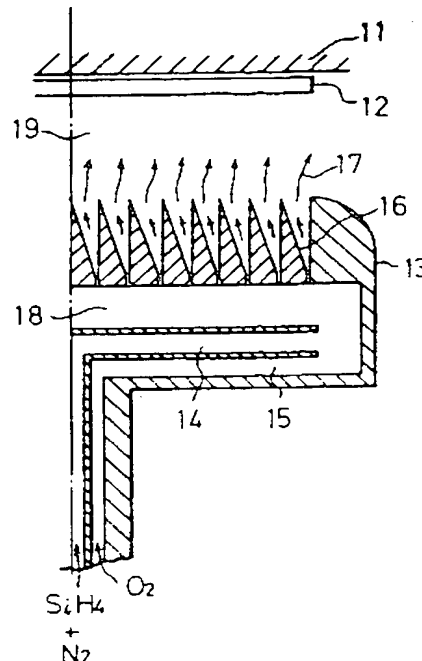


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ABSTRACT : PURPOSE: To improve the manufacturing yield of a device by forming many gas-blowoff holes of a showering means into V-shaped groove state and joining respective ends of the neighboring V-shaped grooves so as to prevent the flowing back of a reactant gas and the resulting growth of granular substances on the shower.

CONSTITUTION: In a CVD apparatus, the gas-blowoff holes 16 of a shower 13 are formed into V-shaped grooves, and respective V-shaped grooves are joined to neighboring V-shaped grooves at respective ends of the openings of the V-shaped grooves. Reactant gases blown out through respective gas-blowoff holes 16 mentioned above having the above constitution form gas flows, respectively, each in a breadth of the opening of the V-shaped groove, by which the gases are uniformly blown out from the whole surface of a shower plane as the whole of the shower 13. Accordingly, the flowing back of the reactant gas in the vicinity of a wafer 12 toward the shower plane can be prevented. By this method, stable operation can be carried out over a long period.

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